

INFORMATION DISCLOSURE CITATION IN AN APPLICATION  (PTO-1449)			ATTY. DOCKET NO. <b>49959-118</b>	SERIAL NO. <b>09/645,690</b>			
			APPLICANT <b>Lizhong Sun, et al.</b>				
			FILING DATE <b>August 24, 2000</b>	GROUP <b>2812 1746</b>			
<b>U.S. PATENTED DOCUMENTS</b>							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
sw	3,889,753	6/17/1975	Richardson				
	4,090,563	5/23/1978	Lybarger, et al.				
	4,541,945	9/17/1985	Anderson, et al.				
	4,954,142	9/4/1990	Carr, et al.				
	5,084,071	1/28/1992	Nenadic, et al.				
	5,225,034	7/6/1993	Yu, et al.				
	5,340,370	8/23/1994	Cadien, et al.				
	5,478,436	12/26/1995	Winebarger, et al.				
	5,527,423	6/18/1996	Neville, et al.				
	5,645,682	7/8/1997	Skrovan				
	5,662,769	9/2/1997	Schonauer, et al.				
	5,509,970	4/23/1996	Shiramizu				
	5,876,508	3/2/1999	Wu, et al.				
↓	5,879,226	3/9/1999	Robinson				
<b>FOREIGN PATENT DOCUMENTS</b>						Translation	
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Yes	No
sw	0 401 147	12/5/1990	EPO				
	39 39 661	6/13/1991	DE				
	0 496 605	7/29/1992	EPO				
	2 722 511	1/19/1996	FR				
↓	0 860 860	8/26/1998	EPO				
<b>OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)</b>							
sw	Hymes, et al., "The Challenges of the Copper CMP Clean", <i>Semiconductor International</i> , pp. 117-122 (1998).						
	Pak, "Impact of EDTA on Junction and Photolith Qualities", <i>Extended Abstracts</i> , October 1980, vol. 80, no. 2, pp 1241-1243.						
EXAMINER <i>Swanson</i>	DATE CONSIDERED <b>8/10/02</b>						

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.